

Figure 1a - UV Absorption of Combustion Gases

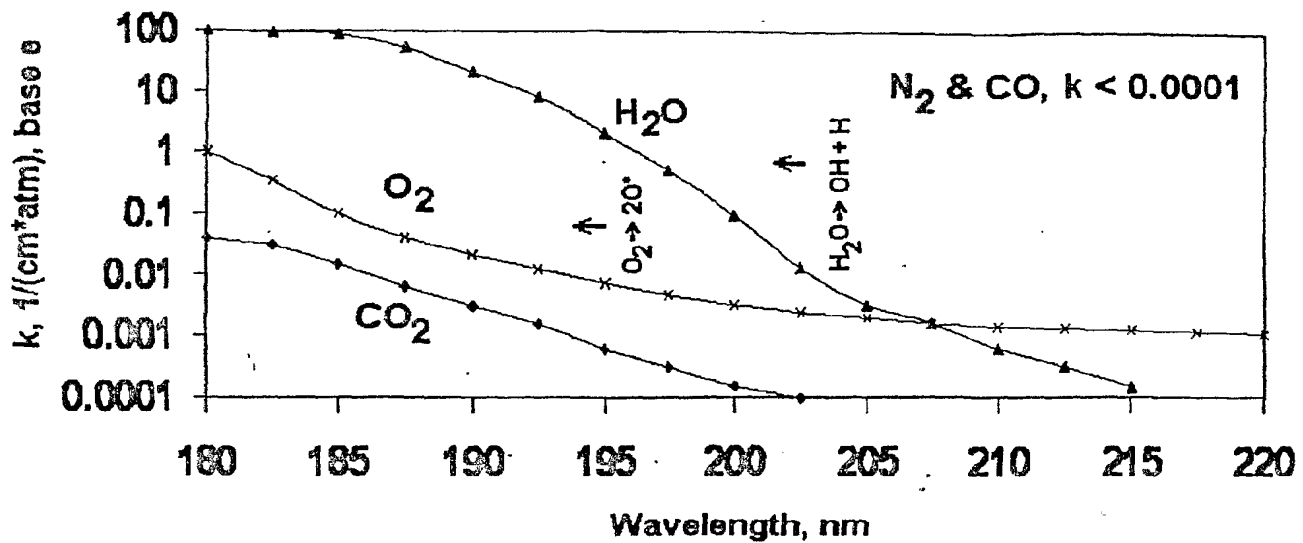


Figure 1b - UV Absorption of Nitrogen Based Gases

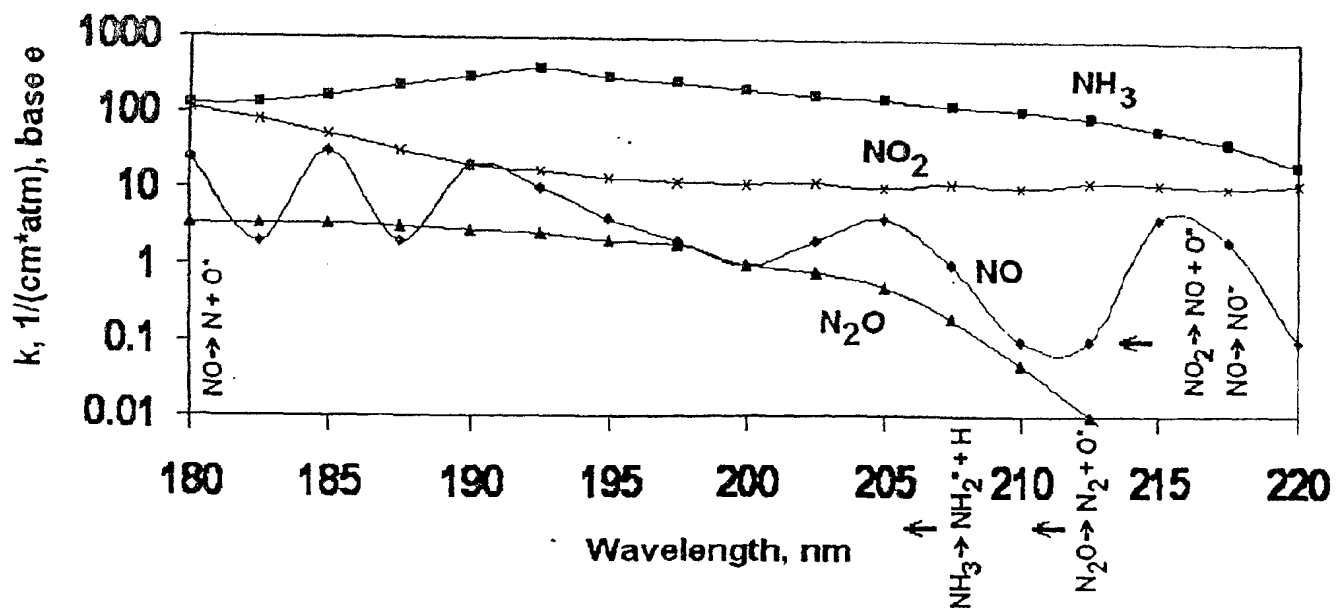
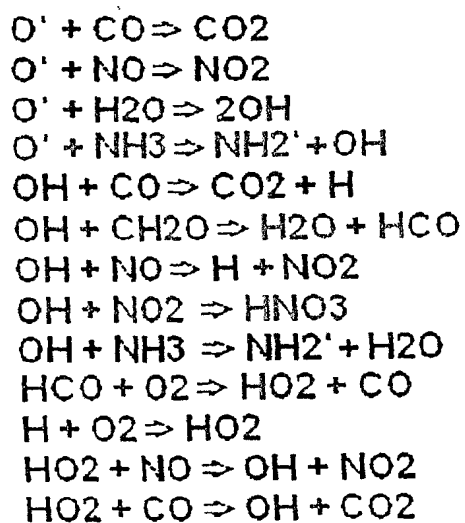
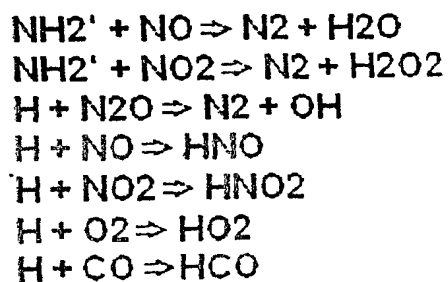


Figure 1c - Important Secondary Reactions

Oxidation



Reduction



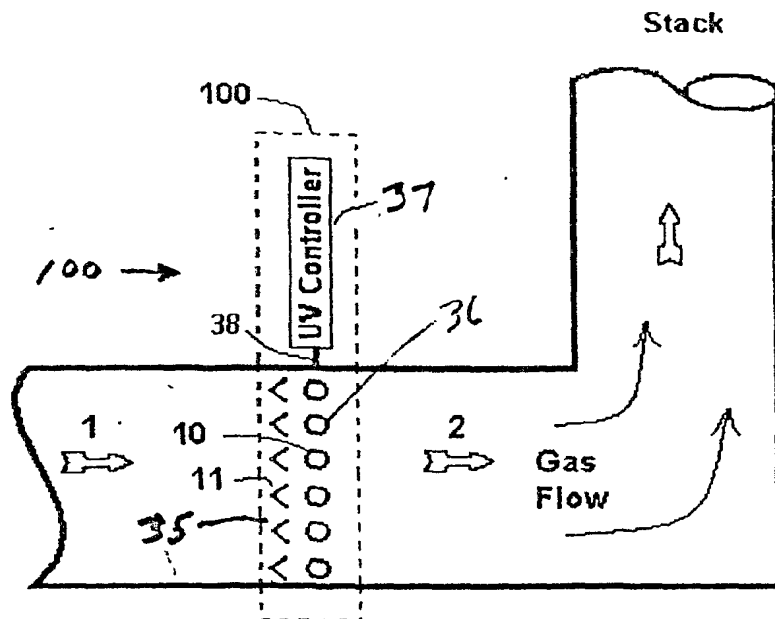


Figure 2a - Use of SUVR to Destroy Combustion Contaminants and/or VOC's

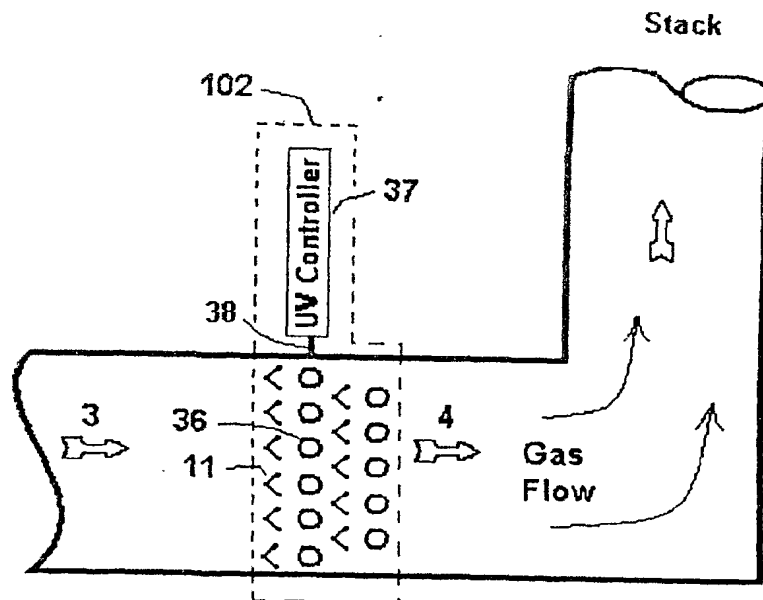


Figure 2b - Use of SUVR to Polish Residual NO_x and NH_3 Gases from an Upstream SNCR, SHR, or SCR Process

**Figure 3a - SUVR to Control Combustion
Contaminants and/or VOC's
plus NO_x Emissions**

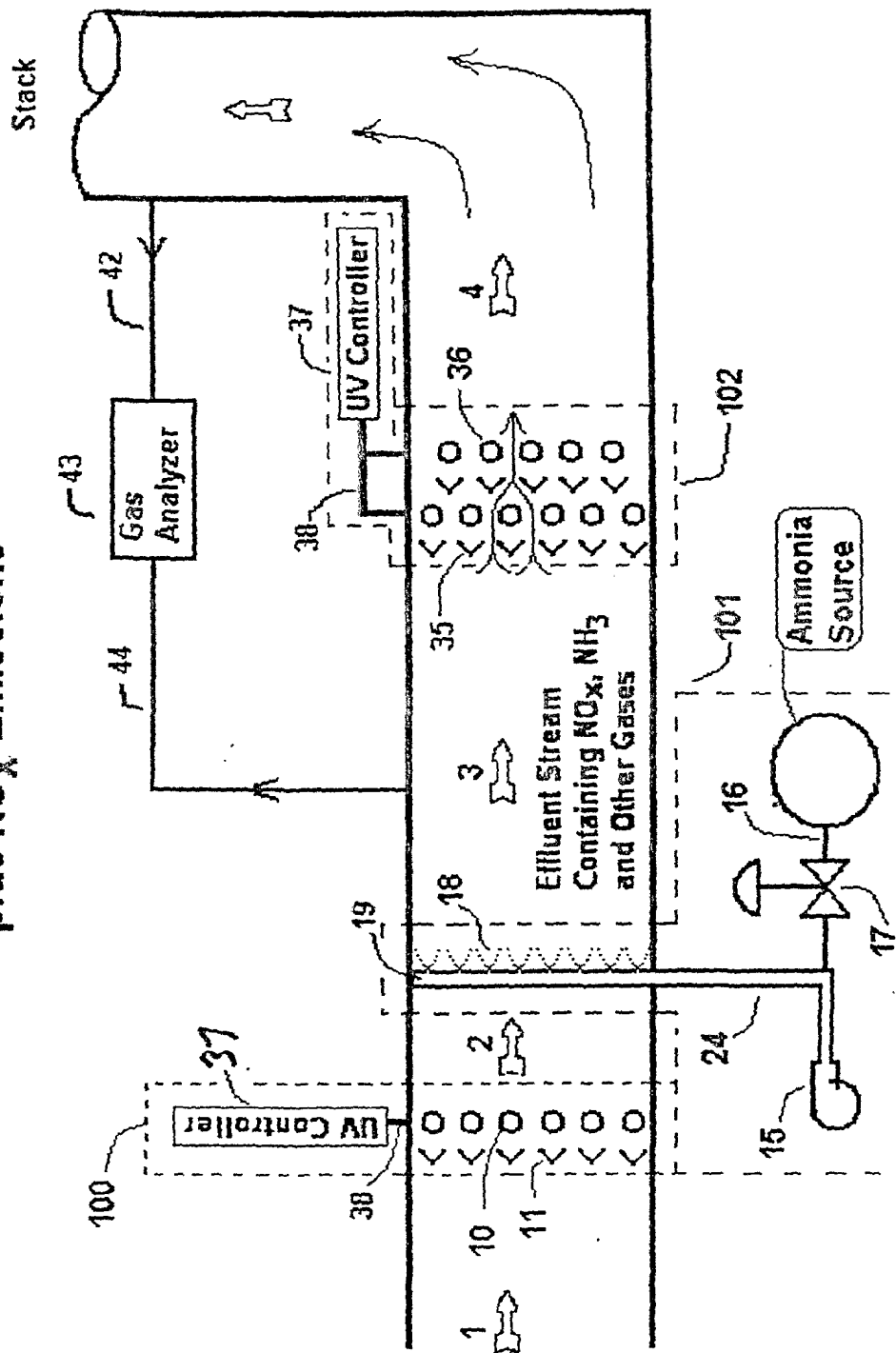
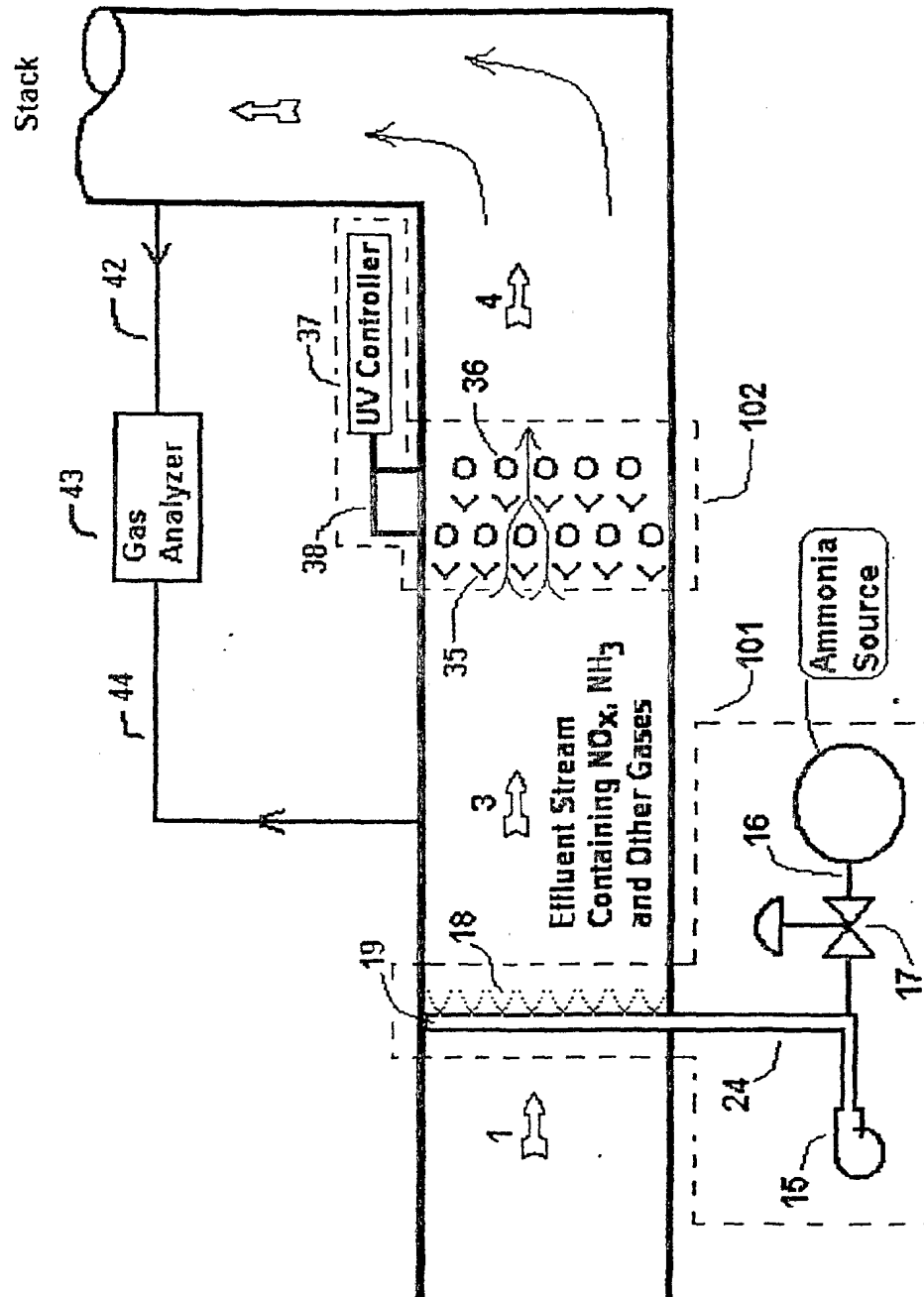


Figure 3b - SUVR to Control NO_x Emissions

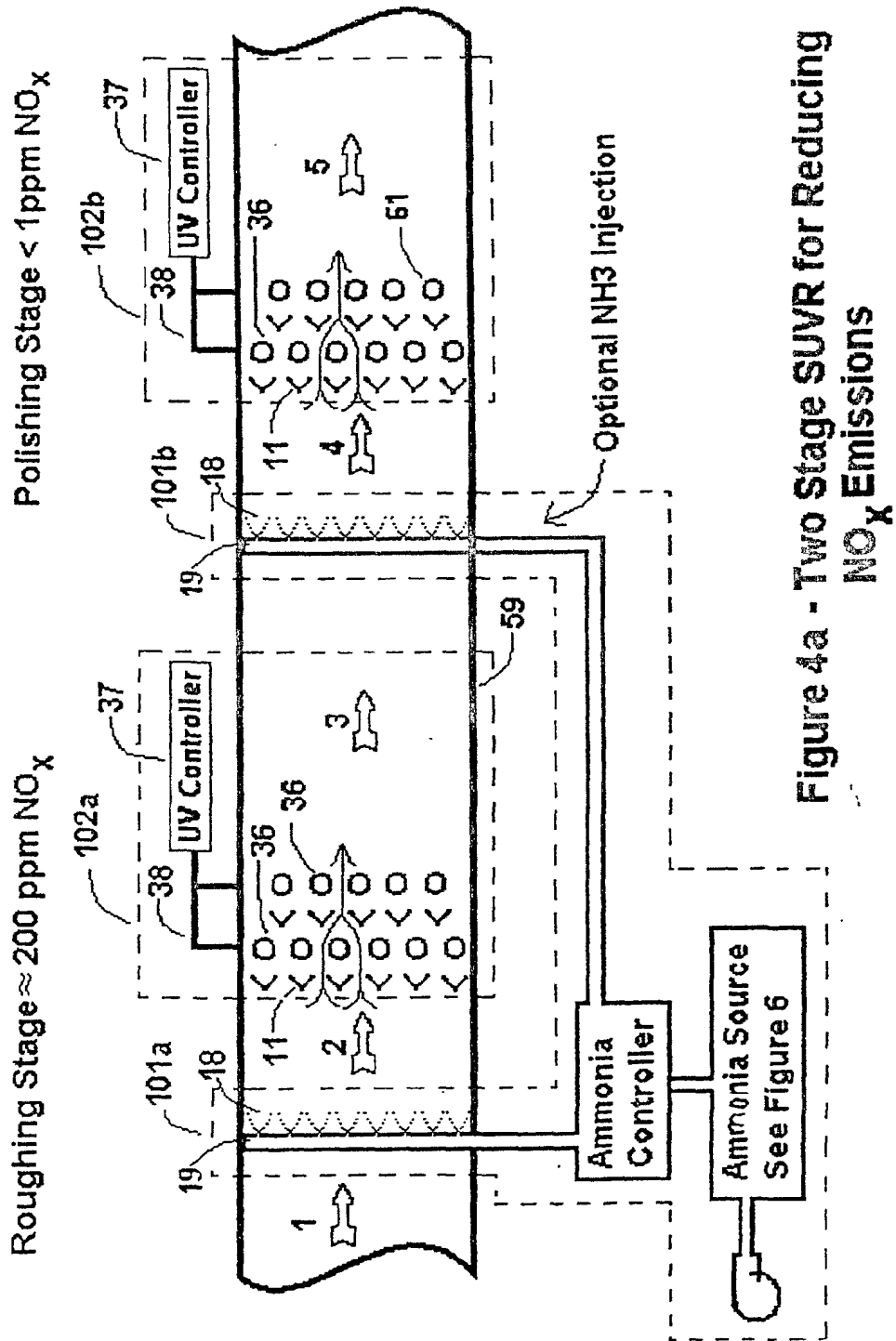


Figure 4a - Two Stage SUVR for Reducing NO_x Emissions

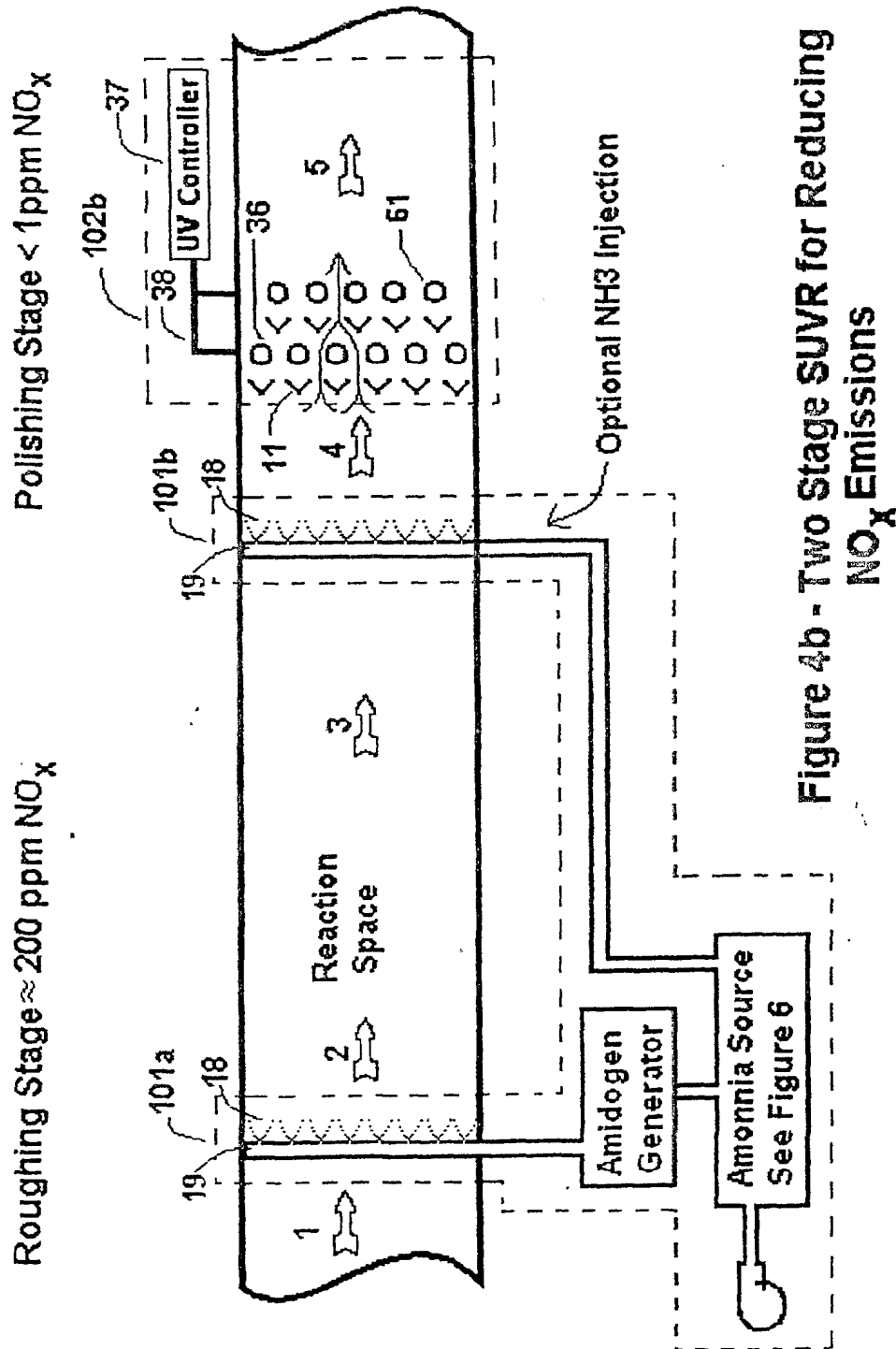


Figure 4b - Two Stage SUVR for Reducing NO_x Emissions

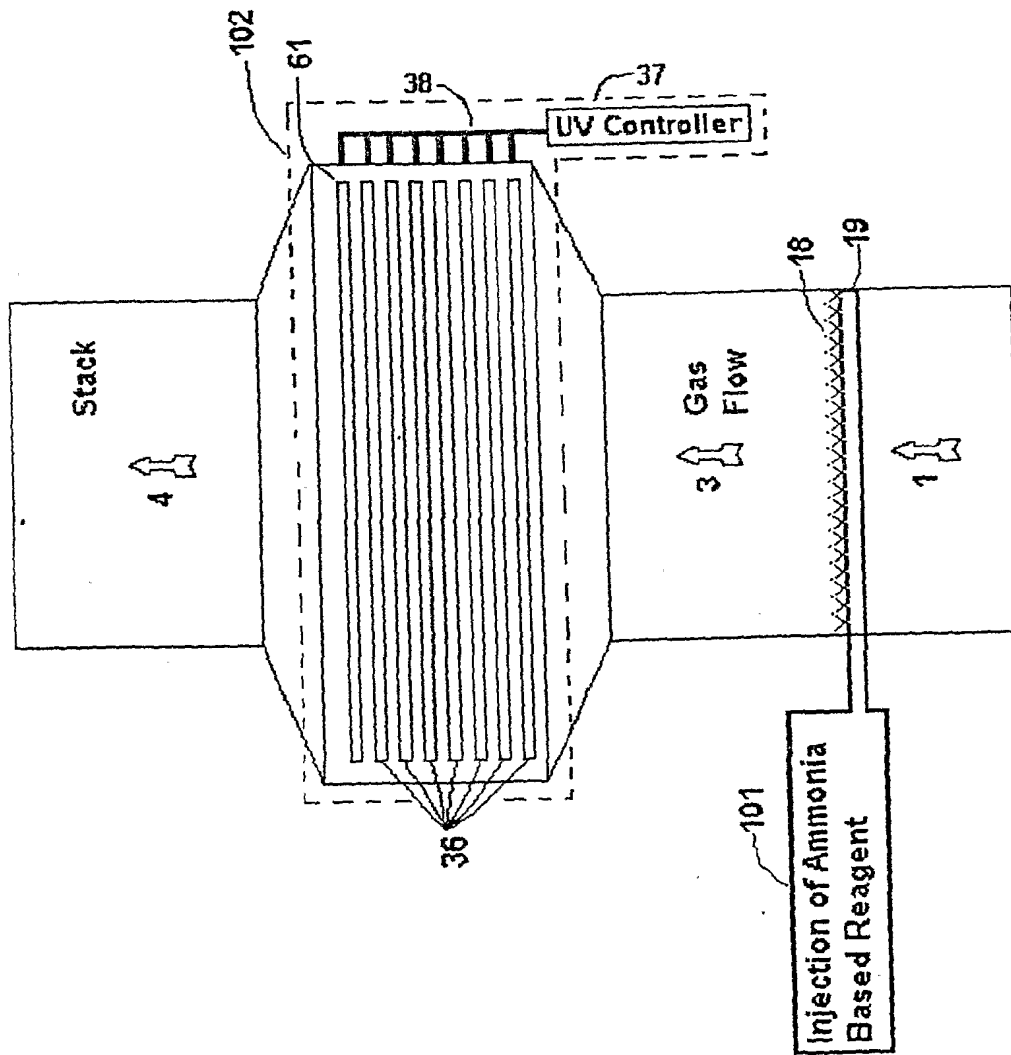
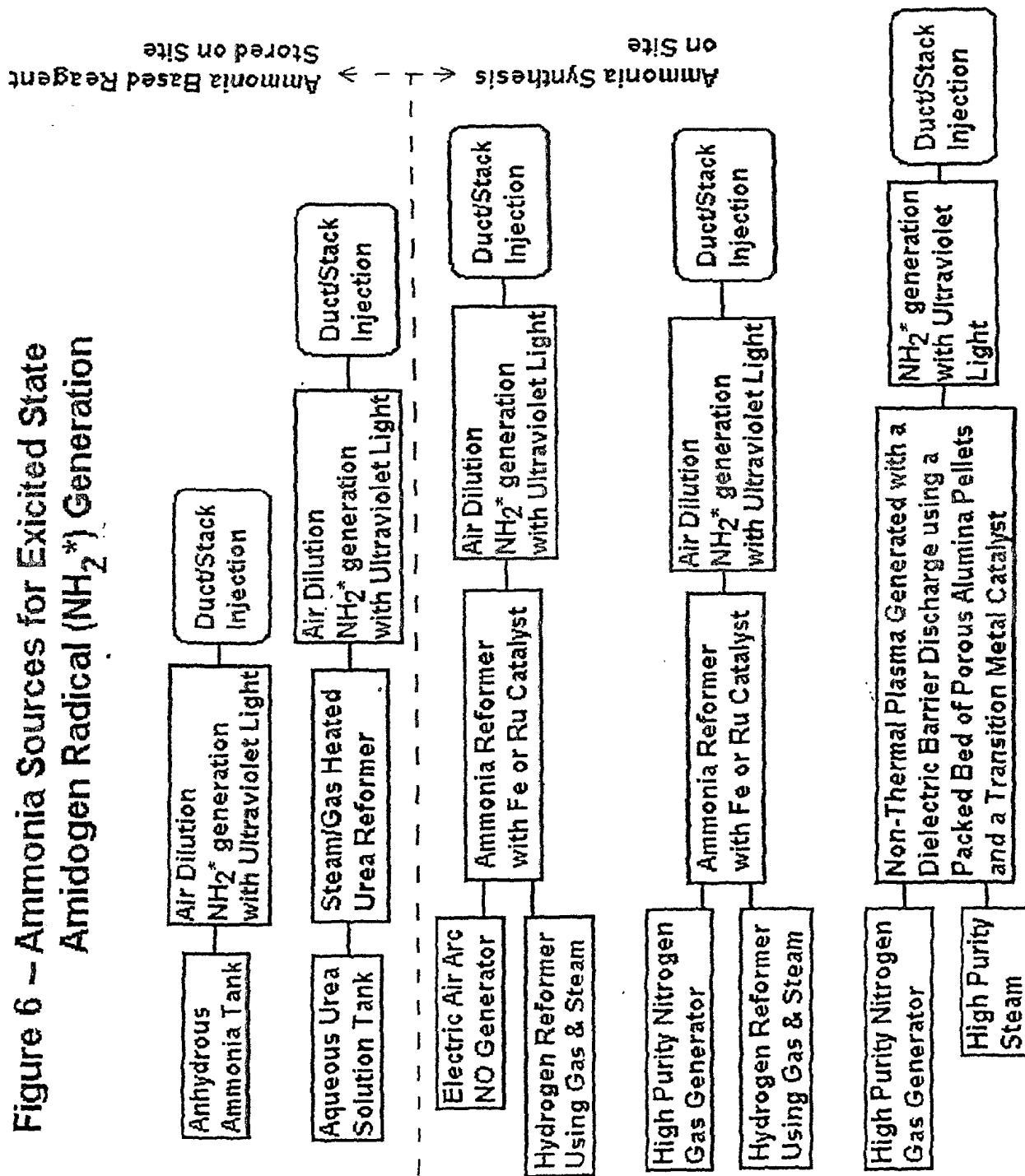


Figure 5 - Installation of the SUVR process on a Combustion Device to Remove NO_x and Residual NH₃ Emissions; Replacing the SCR Process

Figure 6 – Ammonia Sources for Excited State Amidogen Radical (NH_2^*) Generation



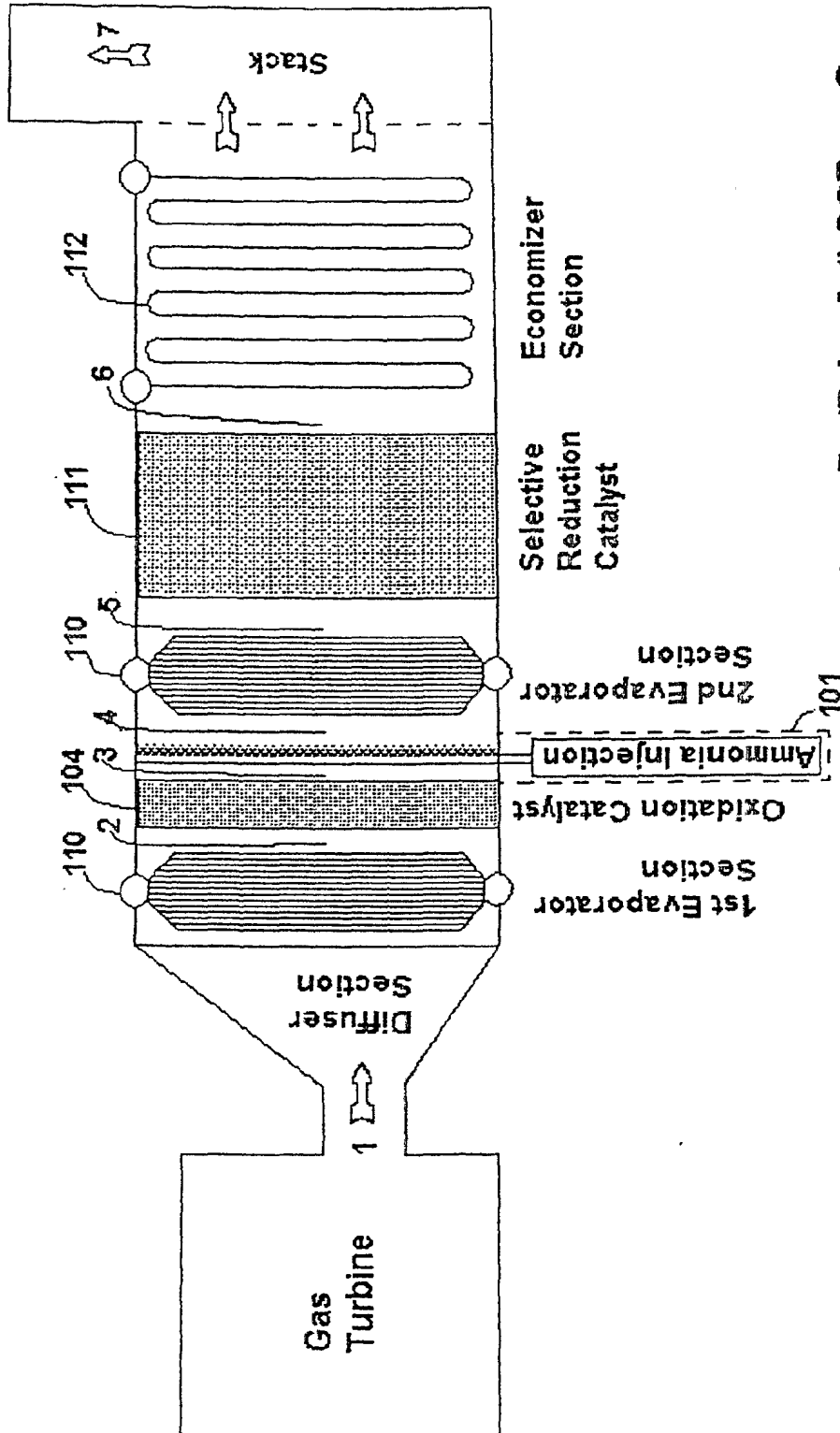
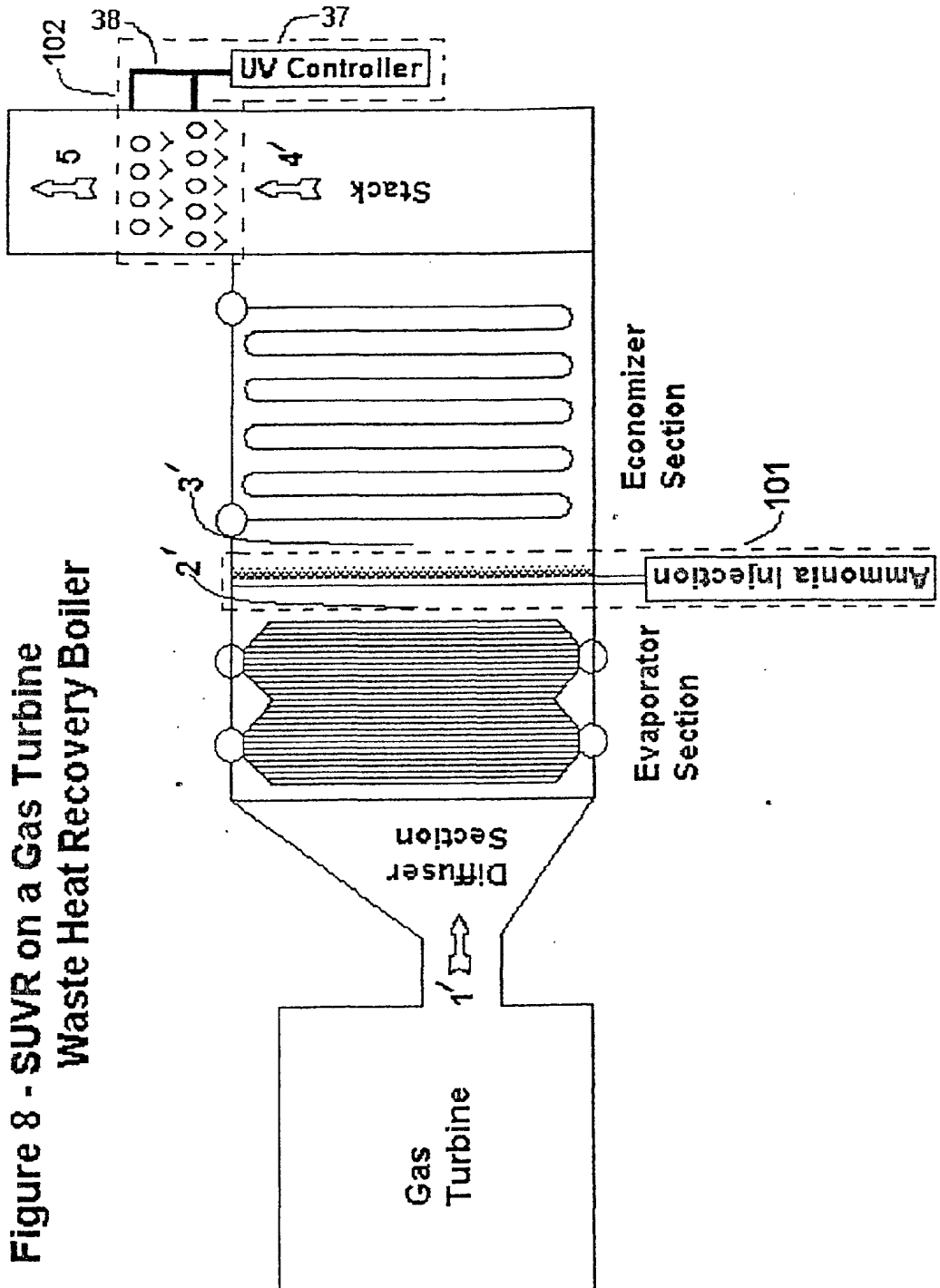


Figure 7 - (Prior Art) SCR on Gas Turbine Waste Heat Recovery Boiler



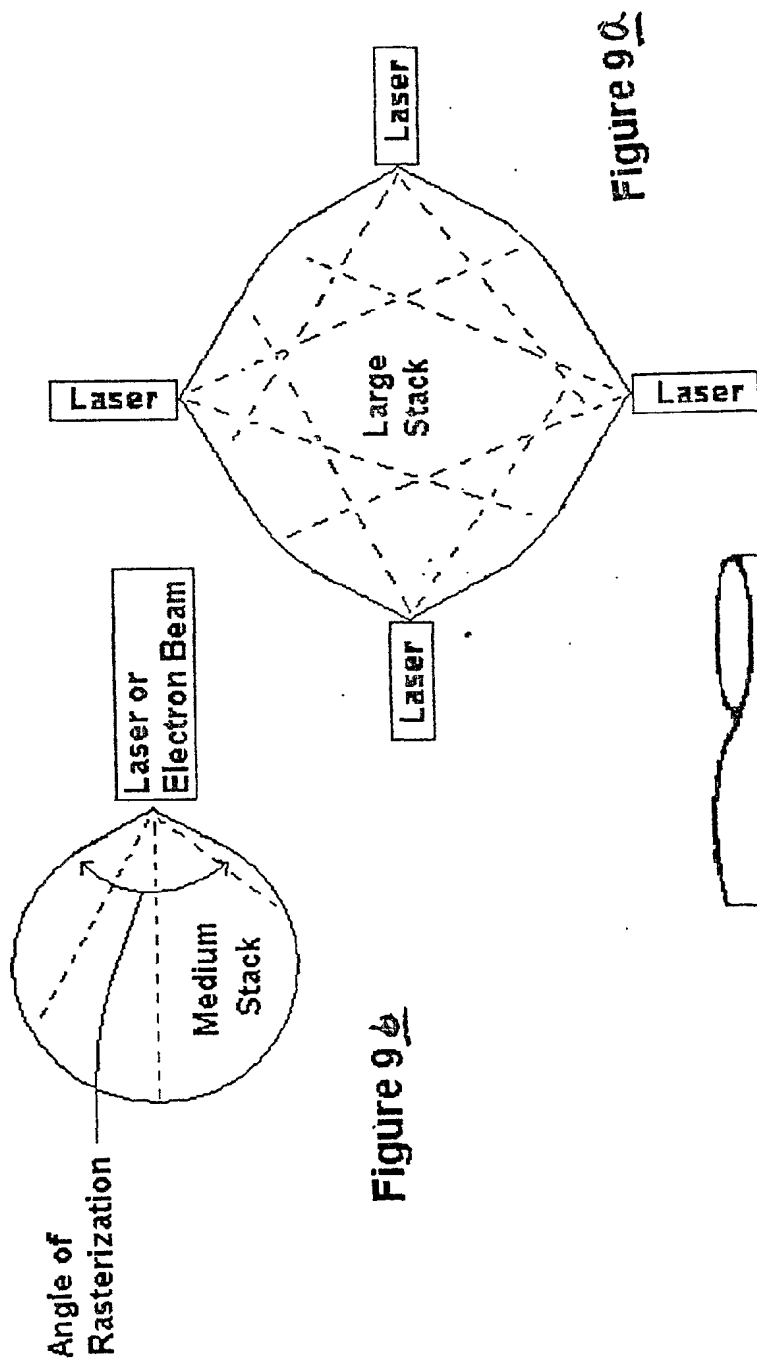


Figure 9a

Figure 9b

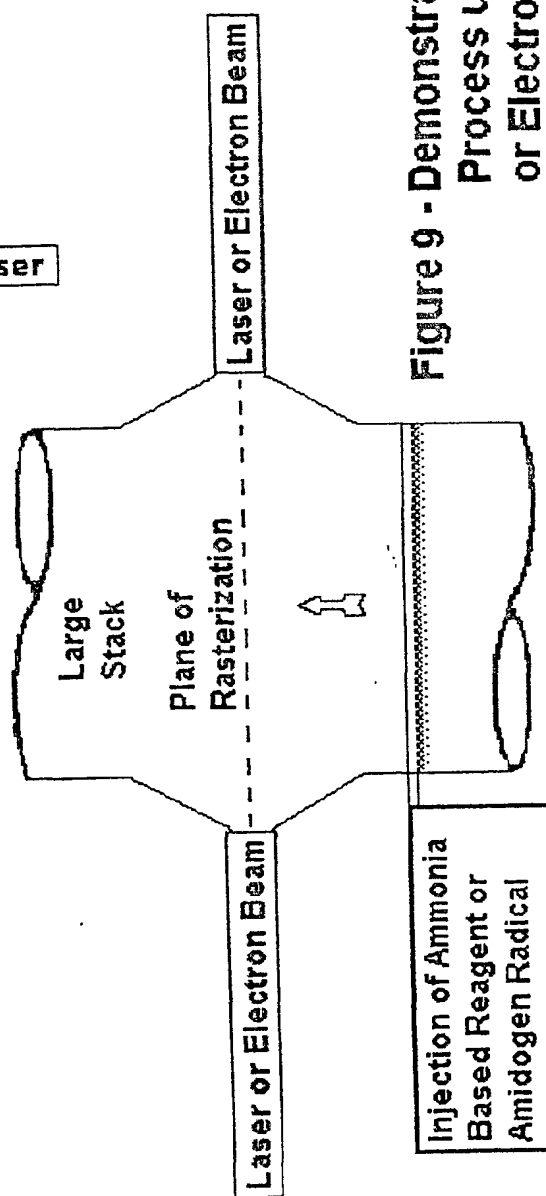


Figure 9 - Demonstration of the SUVR Process using a UV Laser or Electron Beam for Activation

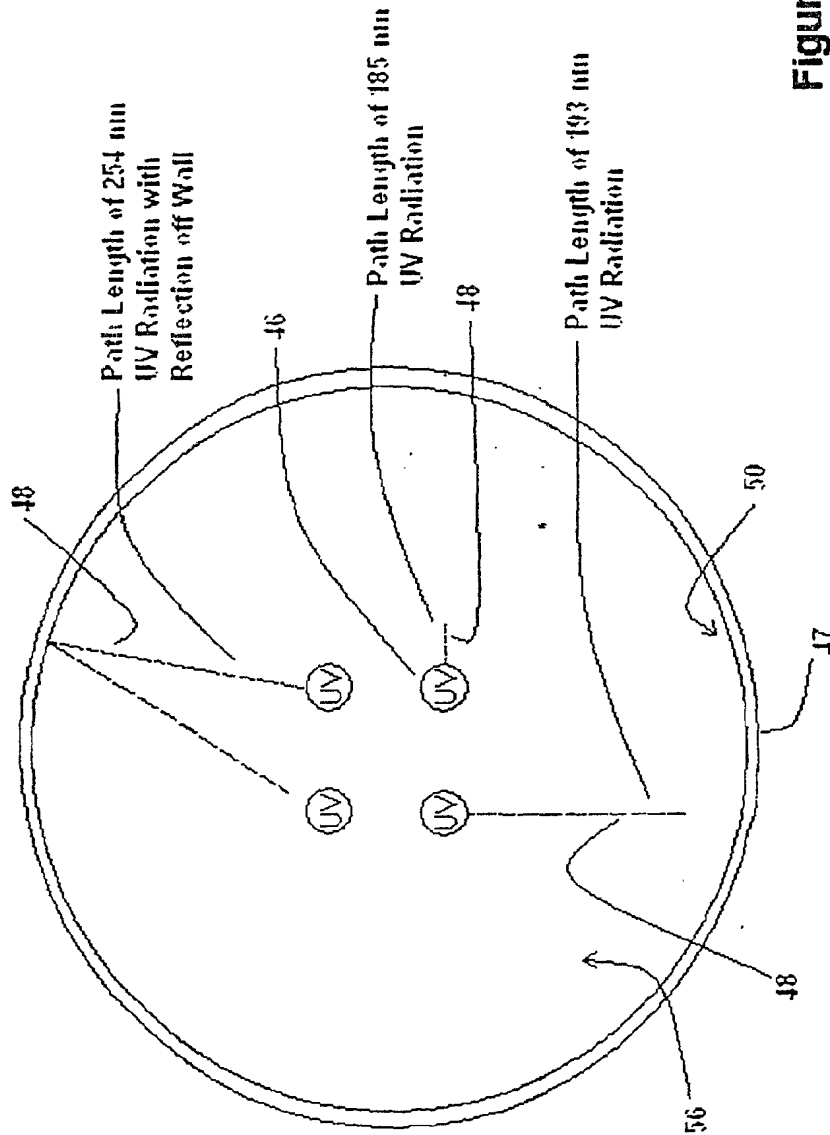


Figure 10

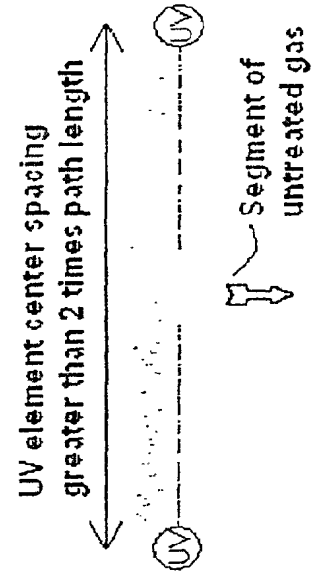
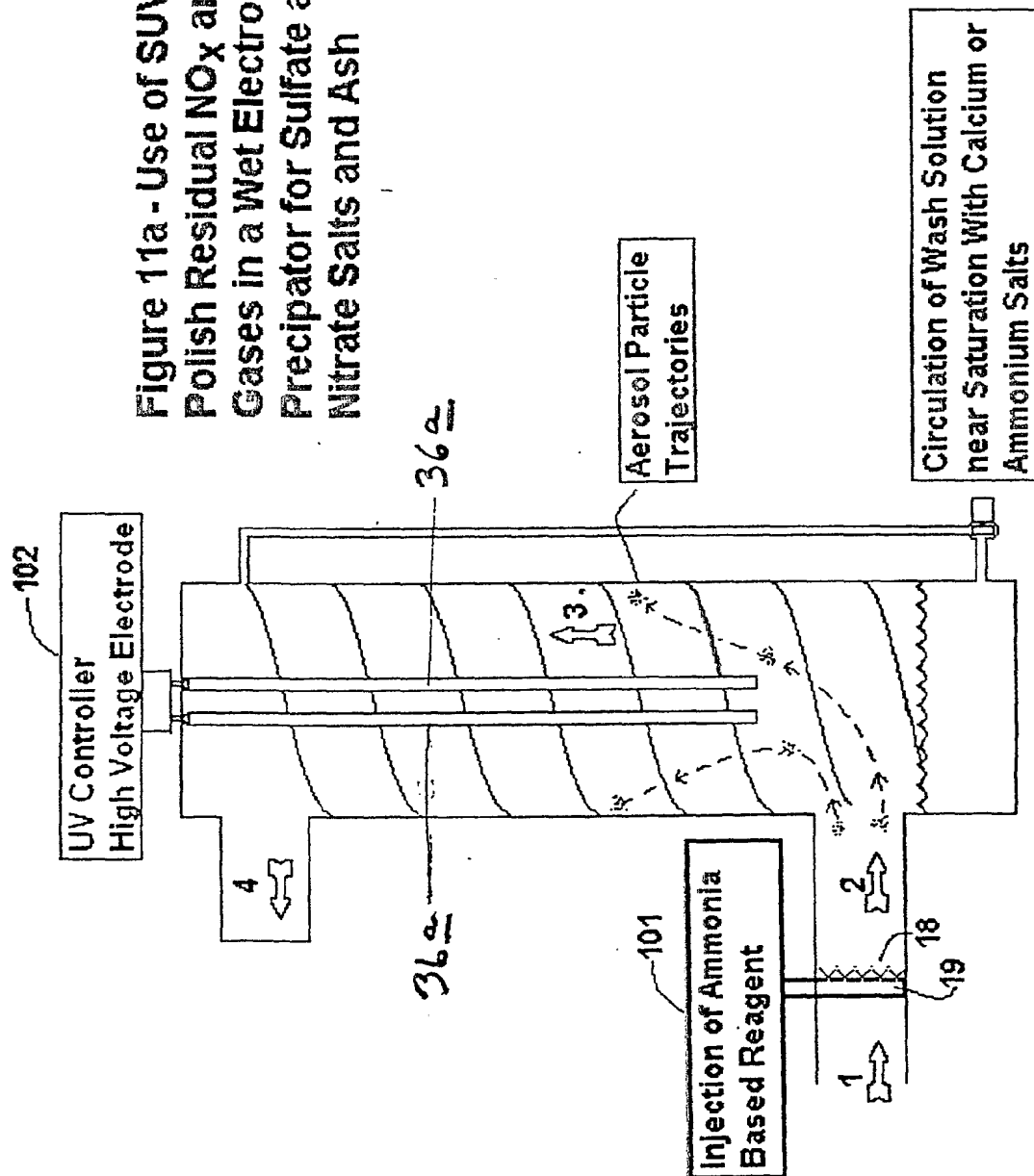


Figure 10 - Relative Transmission Path Lengths of UV lines from a low Pressure Mercury Vapor Lamp

Figure 11a - Use of SUVR to Polish Residual NO_x and NH₃ Gases in a Wet Electrostatic Precipitator for Sulfate and Nitrate Salts and Ash



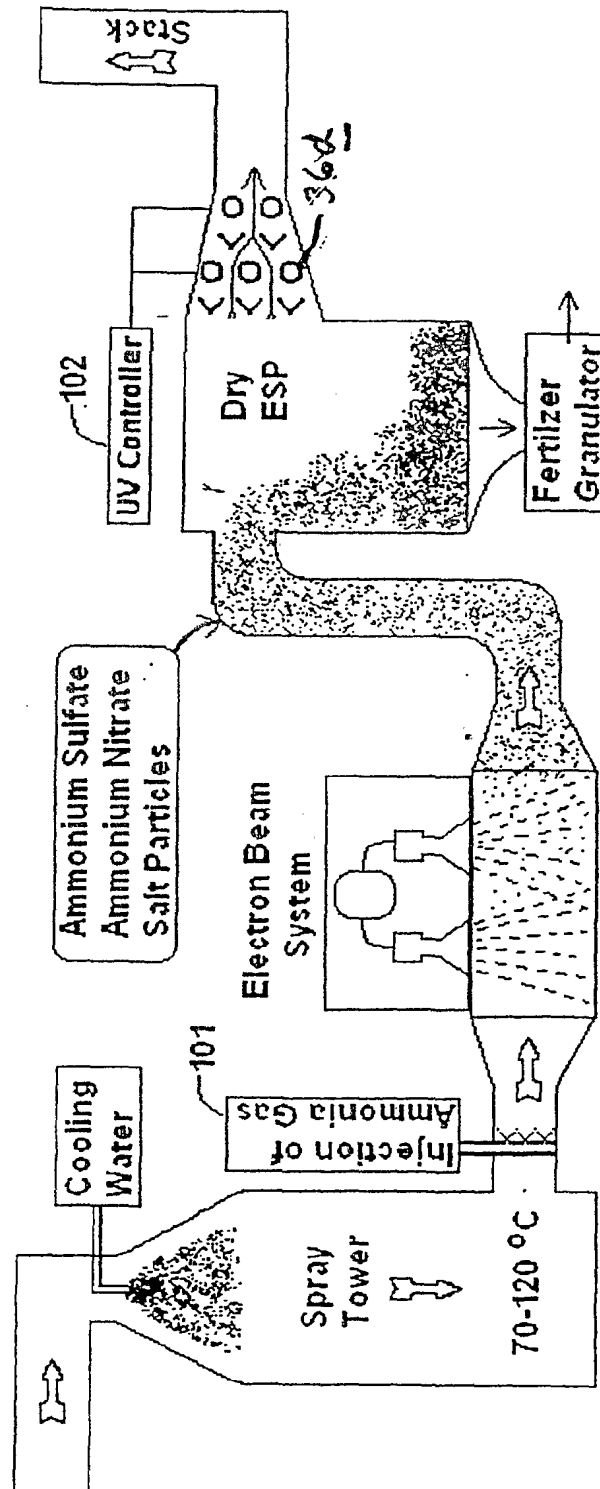
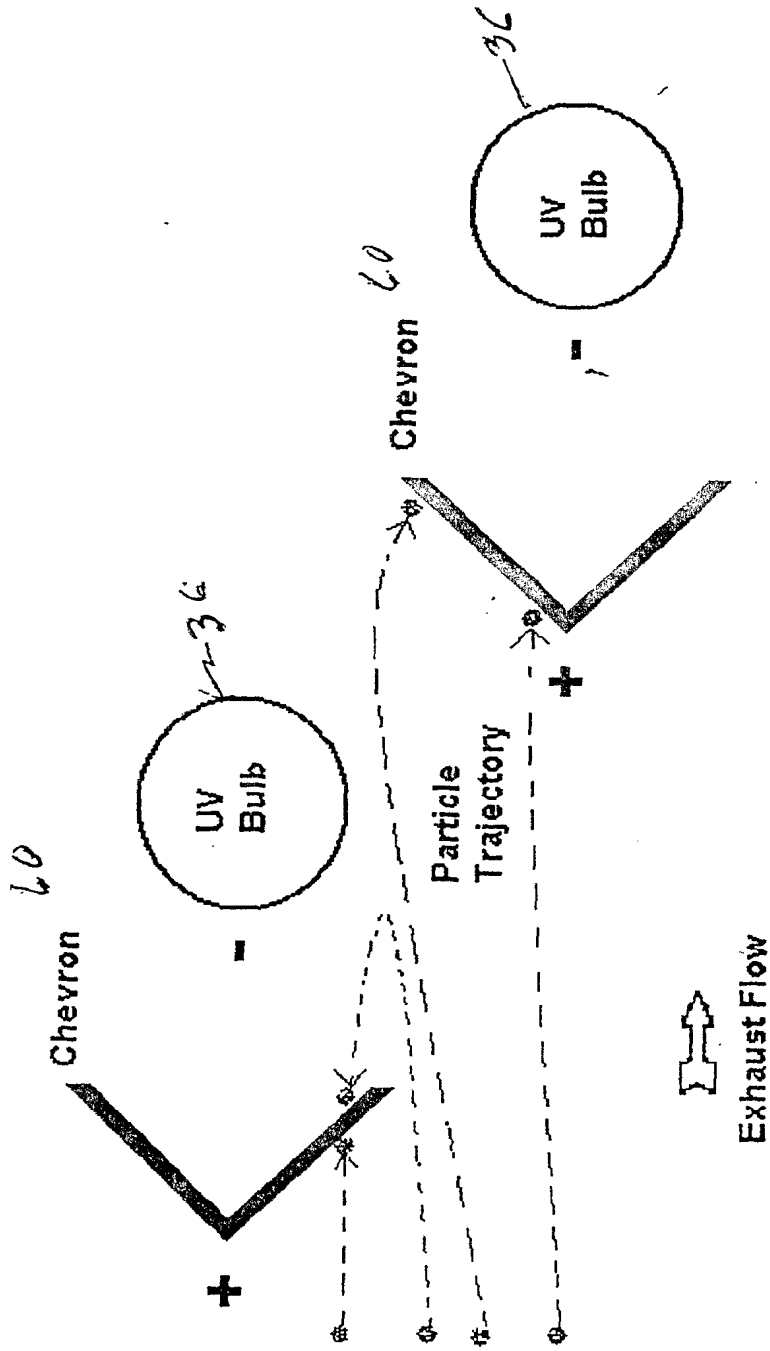


Figure 11b - Use of SUVR to Polish Residual SO_2 , NO_x and NH_3 Gases from an Upstream Electron Beam System to Boost Efficiency to over 99%



**Figure 12 - Electrostatic Field Protection of
Ultraviolet Bulbs in Dirty Exhaust Gases**

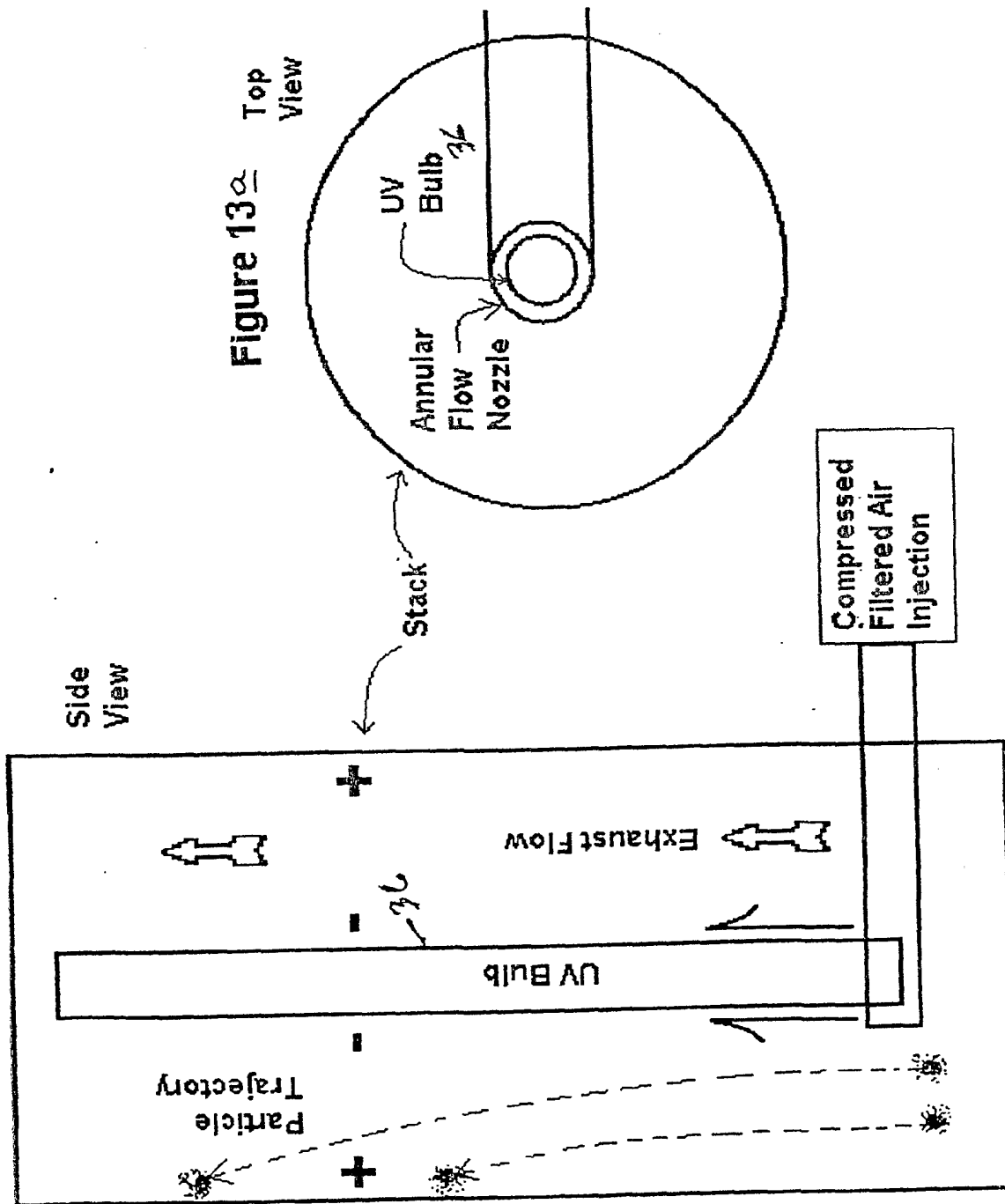


Figure 13 - Electrostatic Field + Boundary Layer of Clean Gas Protection of Ultraviolet Bulb in Very Dirty Exhaust Gases

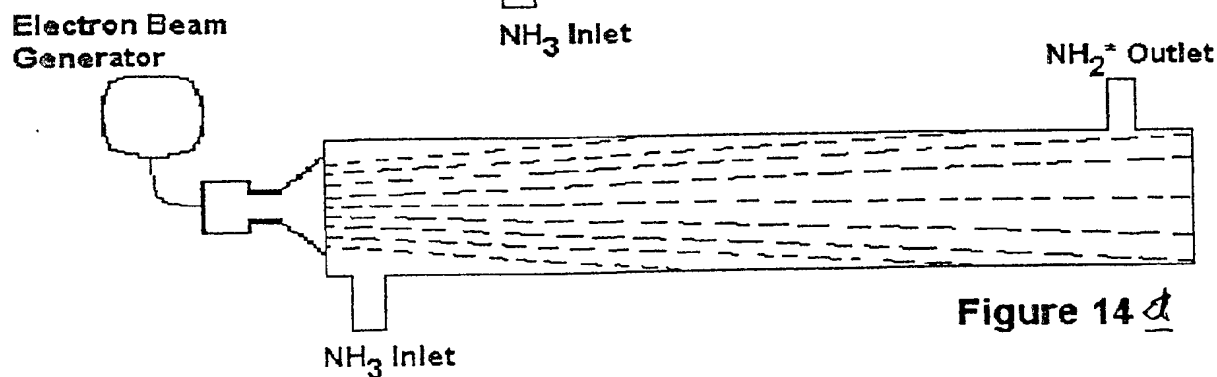
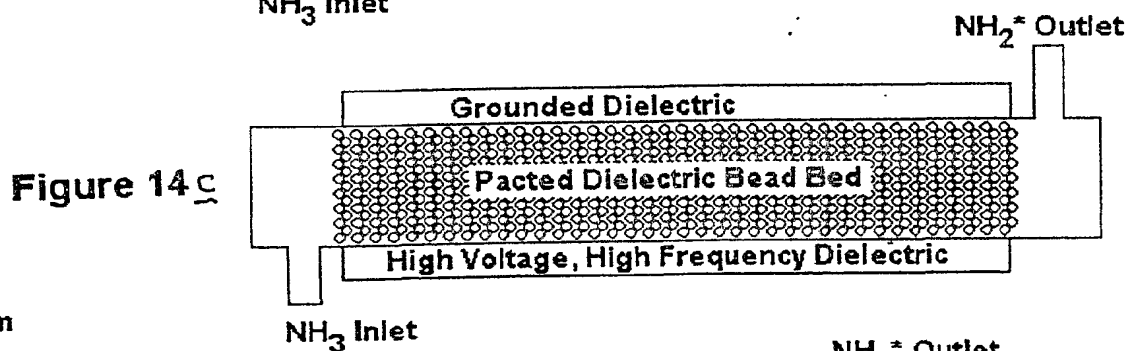
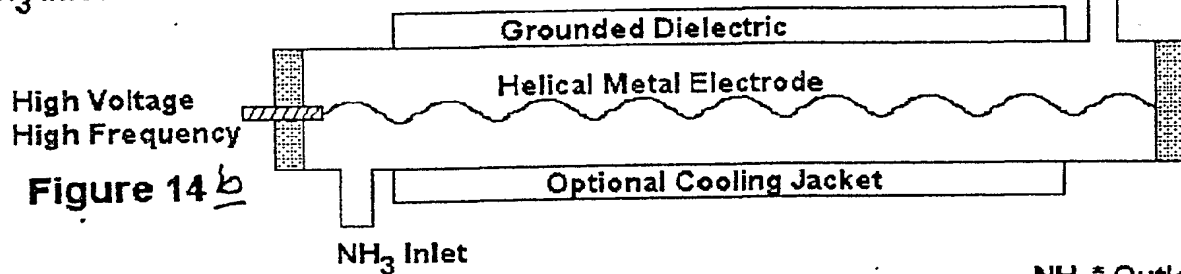
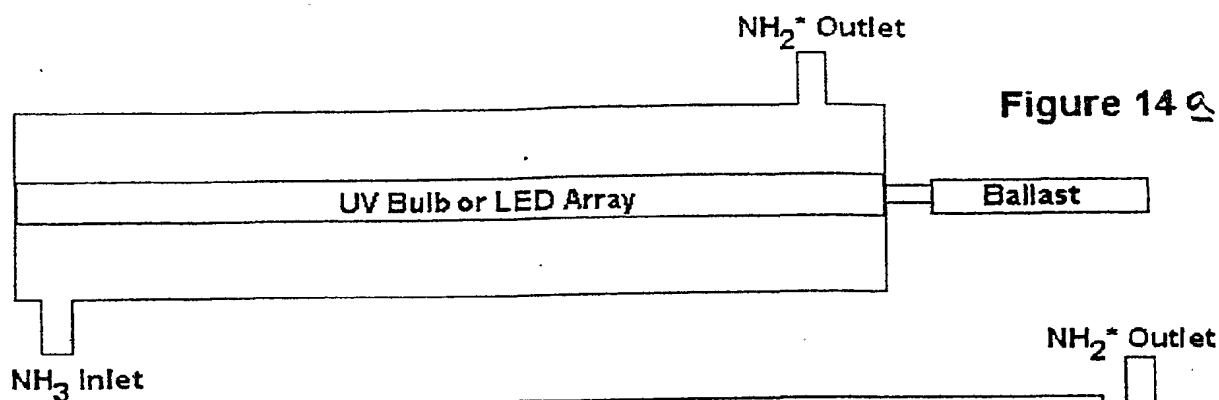


Figure 14 - Amidogen Radical (NH_2^*) Generators

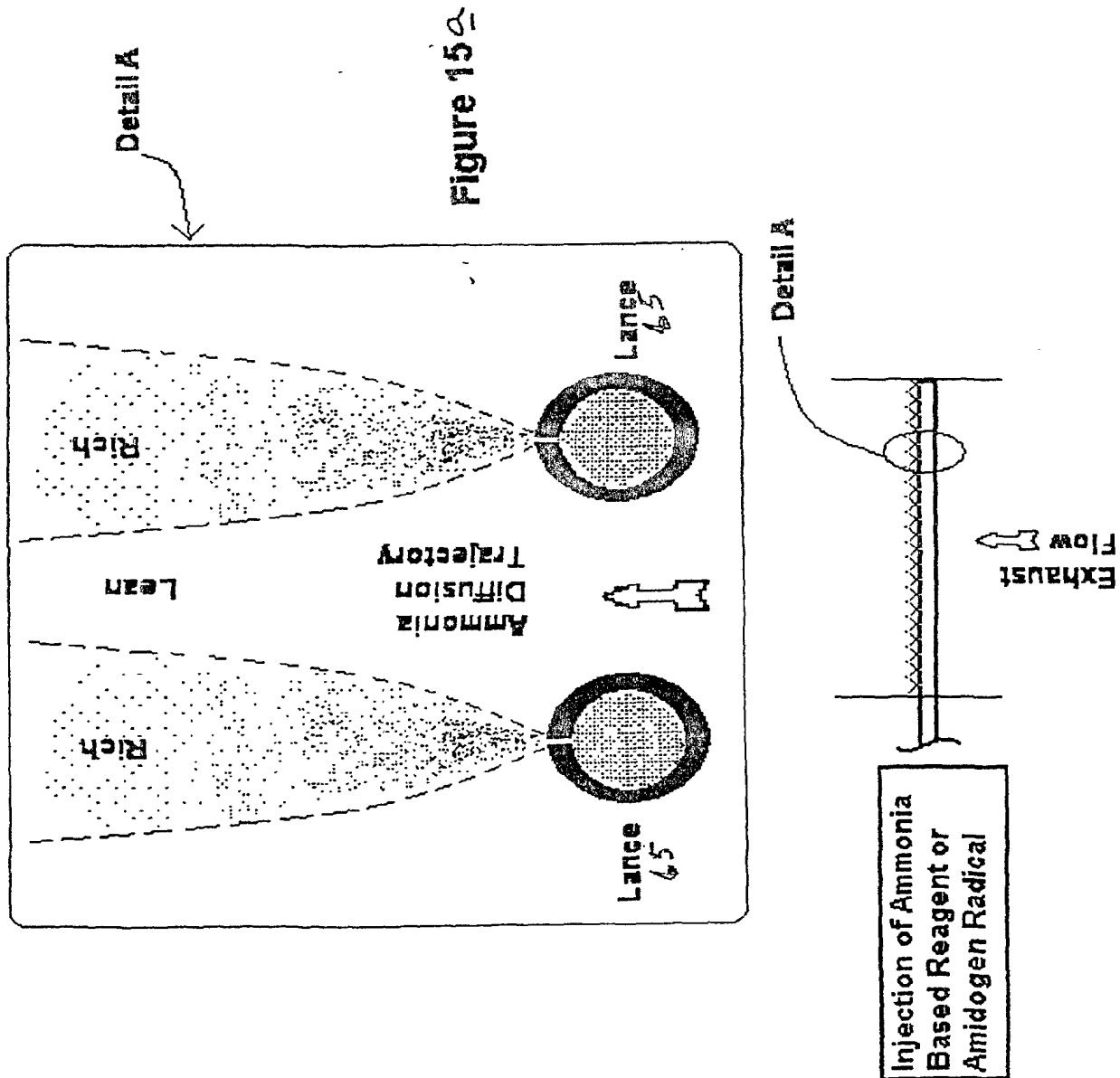


Figure 15 - Demonstration of ammonia gas mixing with lance or wall nozzle injection

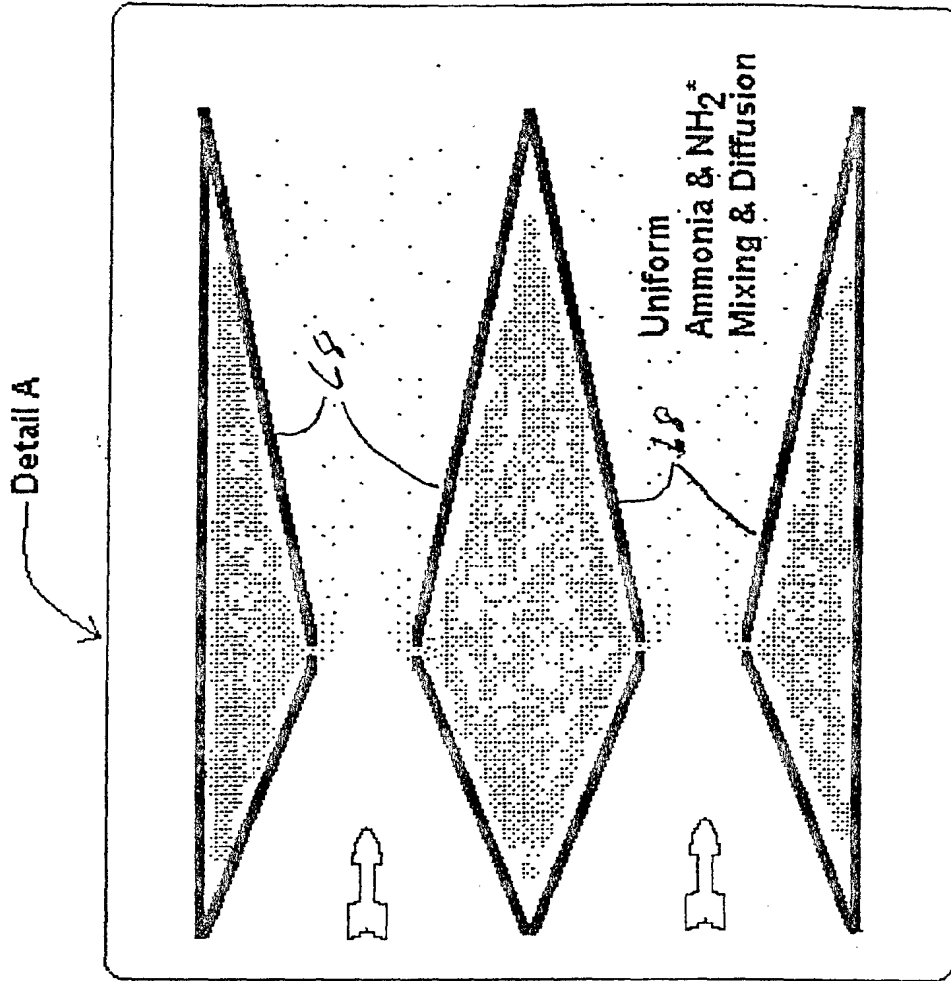
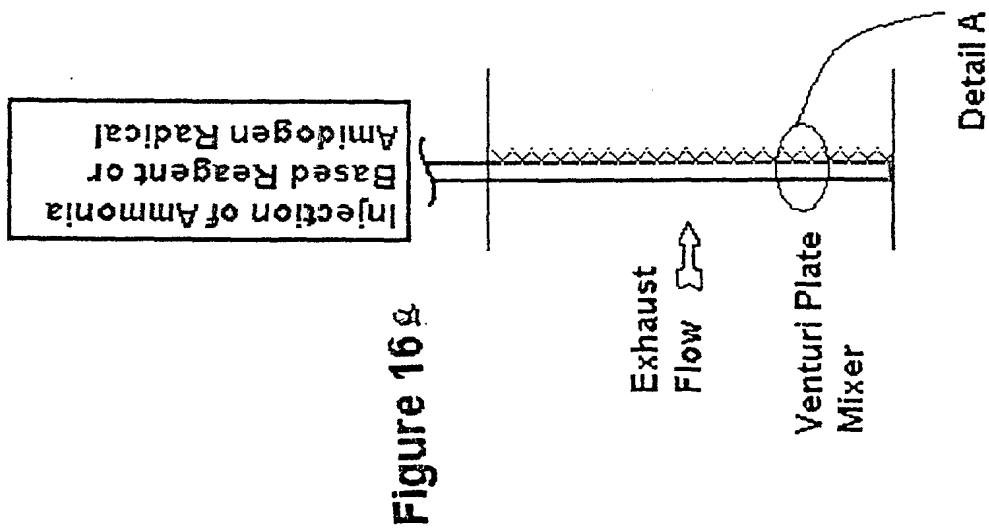


Figure 16 - Demonstration of ammonia gas mixing with a Venturi Plate

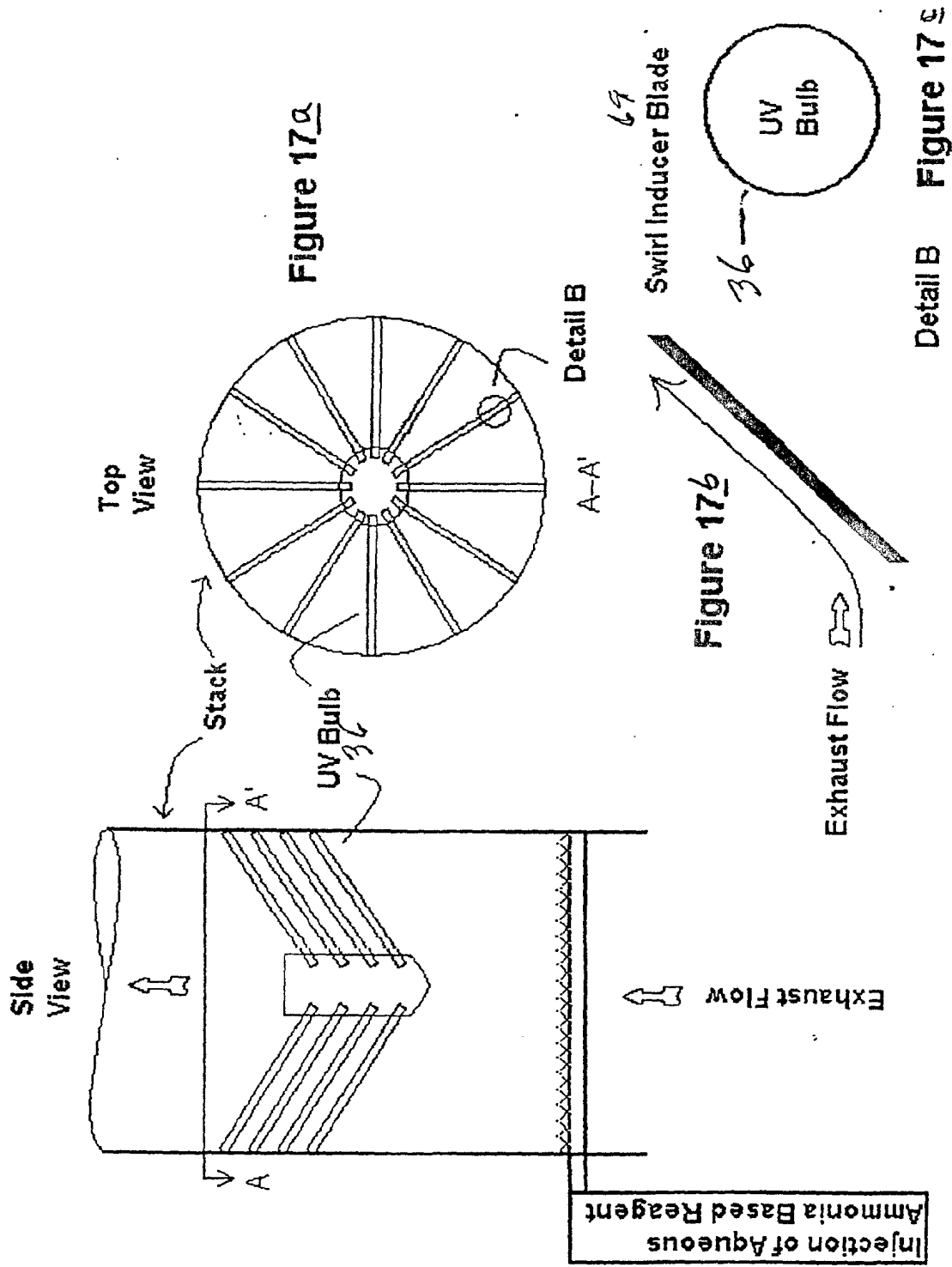


Figure 17 - Installation of the SUVR process on a hot exhaust stack using the vaporization of water to cool the exhaust gases and the thermal decomposition of urea to supply the ammonia

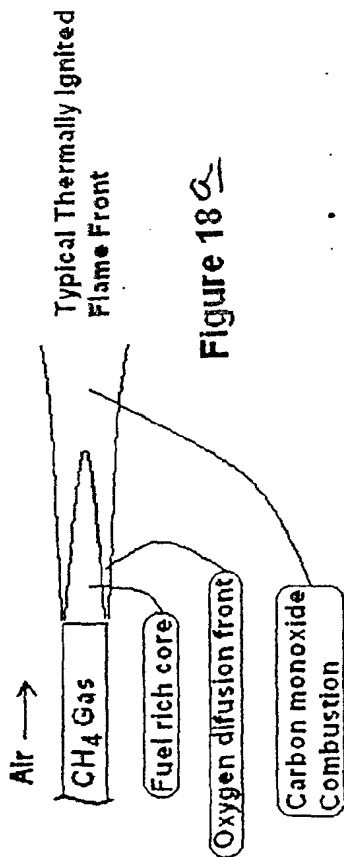


Figure 18 a

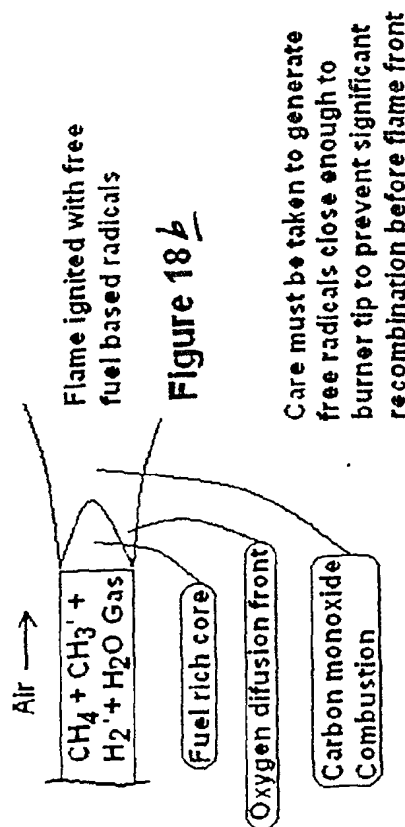


Figure 18 b

Fuel based free radicals generated with the addition of 1-2% air or 1-4% water vapor added to fuel then exposed to ultraviolet light, dielectric barrier discharge, electron beam, or laser discharge.

Liquid Fuel requires longer residence time and higher water vapor content to promote gasification of liquid without coking. Reformer generated hydrogen gas can also be used to dilute liquid fraction.

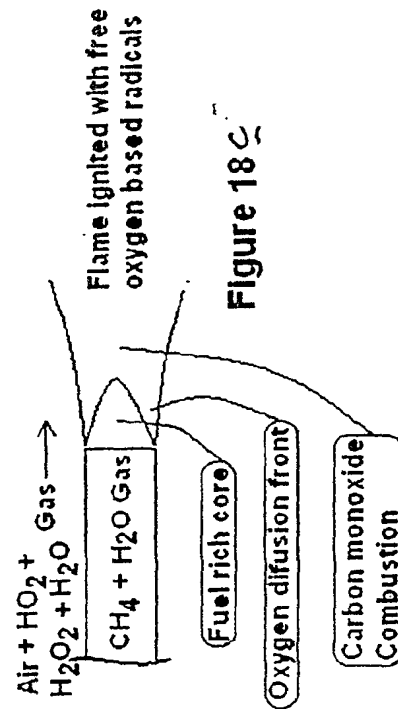


Figure 18 c

Oxygen based free radicals generated with the addition of 1-3% water vapor added to air then exposed to ultraviolet light, dielectric barrier discharge, electron beam, or laser discharge.

Figure 18 - Use of SUVR at burner to reduce VOC emissions. Increase Flame speed, and reduce NOx emissions

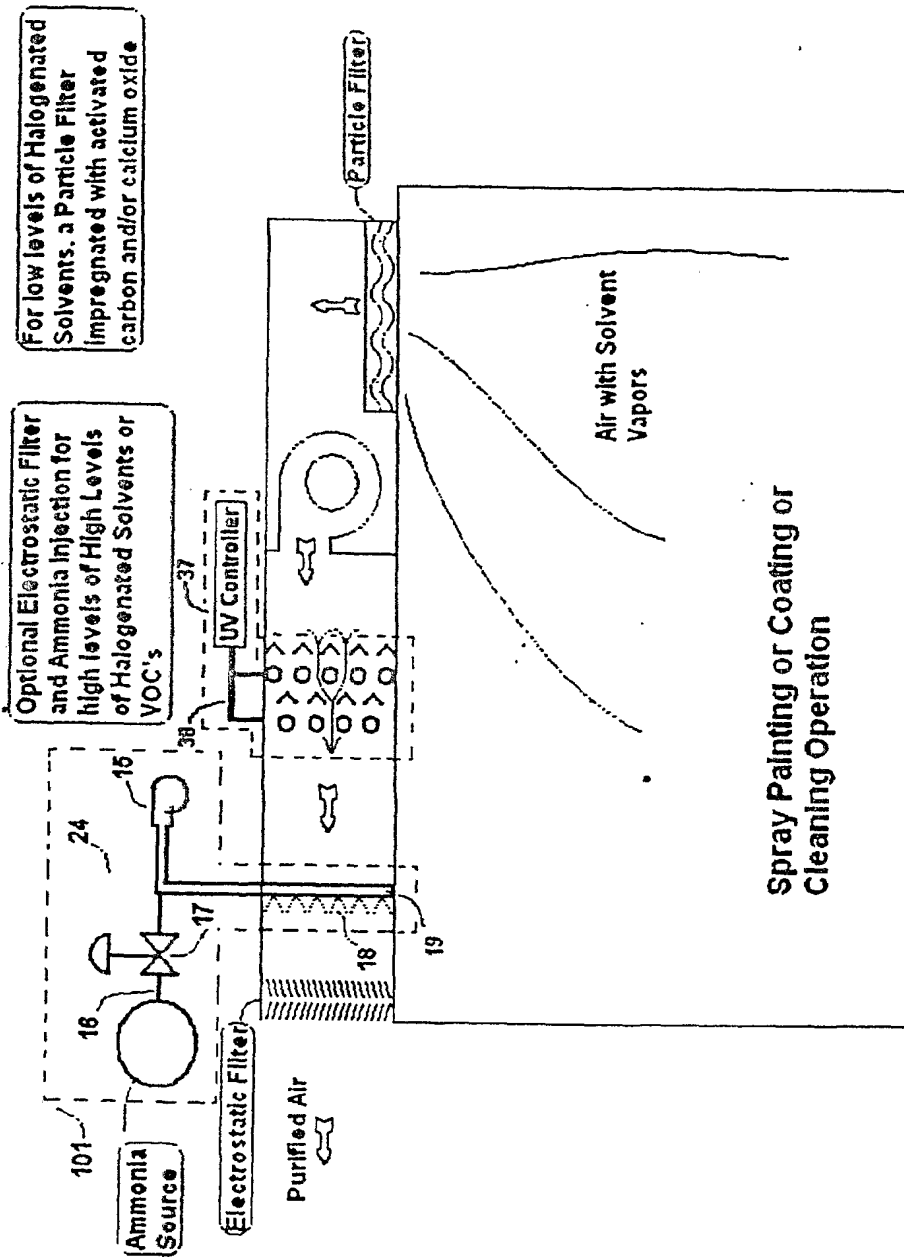


Figure 19 - Organic Compound Destruction Using SUVR with Optional Halogen Acid Removal

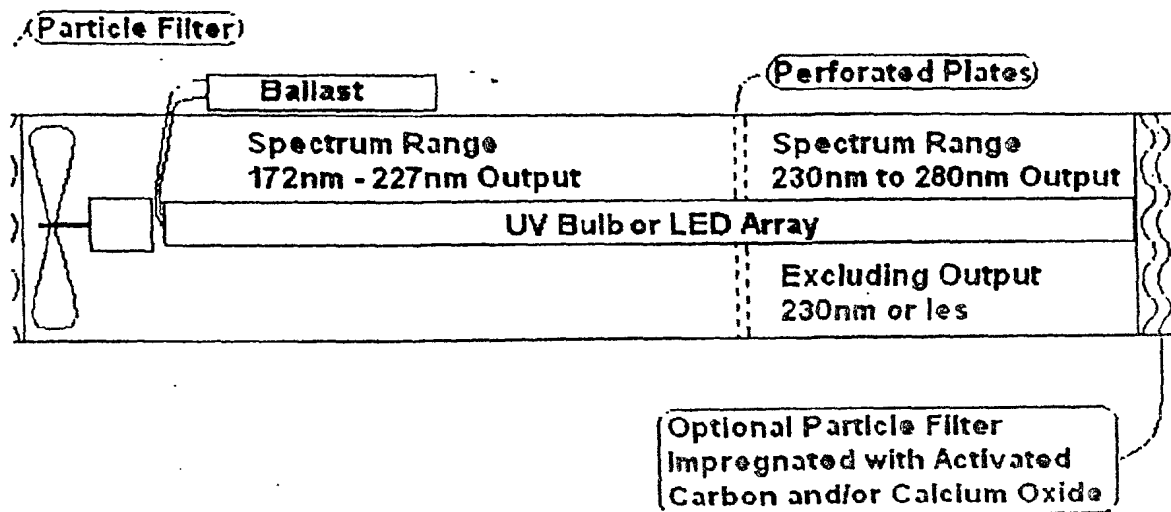


Figure 20 - Portable SUVR unit for Organic Compound Destruction